

## **Erratum**

## Investigation of Cu/TaN Metal Gate for Metal-Oxide-Silicon Devices [Journal of The Electrochemical Society, 150, G22 (2003)]

## Bing-Yue Tsui and Chih-Feng Huang

Department of Electronics Engineering and Institute of Electronics, National Chiao Tung University, Hsinchu, Taiwan

© 2003 The Electrochemical Society. [DOI: 10.1149/1.1566966] All rights reserved. Available electronically March 20, 2003.

Figure 1 (page G22) should appear as:

